



Ms. Rieko Nishimura

(NuFlare Tech. Inc., Japan)

Rieko Nishimura is a senior manager of the Mask Lithography Strategy & Planning Department and a leader of the Technical Marketing Group.

She started her career as a Mask Writer engineer for the Electronic Optical Systems and developed Single Variable Shaping electron-Beam Mask Writers (SVSB) at Toshiba Machine Co., Ltd. She joined Nuflare Technology, Inc. when it was established as the spun off company from the Toshiba Group, and continued the mask writer development. She joined in 2016 the team to develop the first generation electron Multi-Beam Mask Writer (MBM). After successfully having developed the first generation MBM, she continued to work on the development of the following generations writers. Her total career in mask writer development spanned 25 years until she moved to the Mask Lithography Strategy & Planning Department in 2024. She holds a master's degree in science in Bioscience from Teikyo University of science and a bachelor's degree in production engineering from Nihon University. After obtaining her bachelor's degree, she was chosen to train as a research student at the Japan Atomic Energy Research Institute.